

ABSTRACT

POLISHING PAD AND METHOD FOR MANUFACTURING SAME

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The present invention addresses the problem of providing: a polishing pad that is long-lasting, has a high polish rate, and is capable of producing a high degree of flatness on polished articles; and a method for manufacturing the polishing pad. The solution provided is to eliminate a sea component from a non-woven fabric that includes a binder fabric and a sea-island type composite fiber composed of the sea component and an island component, the island component having a diameter of 10-2500 nm, and to add a polymer elastic body to the non-woven fabric.

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[No Available Figure]